



Pall Microelectronics
2200 Northern Boulevard
East Hills, NY 11548

516.484.5400 phone
516.484.5228 fax
800.645.6532 toll free
www.pall.com

PALL'S NEWEST P-NYLON FILTER BRINGS ADVANCED DEFECT-REDUCTION CAPABILITIES TO 193 NM RESISTS

East Hills, NY (July 6, 2005) - - Pall Corporation today introduced its Asymmetric P-Nylon filter to extend 0.02-micron filtration to a broader range of lithography chemistries, including 193 nm and 248 nm photoresists. The asymmetric filter builds on the success of Pall's standard, 0.02-micron-rated P-Nylon filter, which has been proven to significantly reduce defects in bottom anti-reflective coating (BARC) lithography chemistries.

In point-of-use photoresist filtration, lithographers need filters that offer exceptional defect-reducing capabilities yet maintain extremely low pressure during dispensing or chemical processing. The new Asymmetric P-Nylon filter is based on Pall's highly asymmetric membrane pore structure that reduces pressure drop while allowing users to achieve 0.02-micron-level filtration. The application of Pall's asymmetric membrane technology to lithography filtration follows its successful adoption in other critical semiconductor manufacturing processes.

"Over the past several years, our P-Nylon filter technology has pushed the limits of what's possible in lithography filtration," said Steve Chisolm, president of Pall Microelectronics. "The new Asymmetric P-Nylon filter is an extension of our ongoing efforts to reduce defect densities and size in lithography processes, and reflects our continued leadership in lithography filtration today."

Pall offers a complete line of point-of-use and bulk filtration and purification products for a wide range of lithography chemistries, including photoresists, solvents and anti-



reflective coatings. In recent evaluations of the company's line, Pall's products demonstrated significant defect reductions in many lithography applications.

The Asymmetric P-Nylon filter is naturally hydrophilic, enabling fast start-up and minimal microbubbles. The filter is available in several point-of-use capsules and cartridges, including Pall's PhotoKleen™ EZD-3 capsule and Falcon filter configurations. The filter is also available in 10-inch lengths for bulk photoresist production.

Pall Microelectronics is the global leader in filtration, separations and purification technologies for the microelectronics industry. It supports the semiconductor, data storage, fiber optic, advance display and materials markets with a comprehensive suite of contamination control solutions for chemical, gas, water, chemical mechanical polishing and photolithography processes.

About Pall Corporation

Pall Corporation is the leader in the rapidly growing field of filtration, separations and purification. Pall's business is organized around two broad markets: Life Sciences and Industrial. The Company provides leading-edge products to meet the demanding needs of customers in biotechnology, pharmaceutical, transfusion medicine, semiconductor, water purification, aerospace and broad industrial markets. Total revenues are \$1.8 billion. The Company headquarters are in East Hills, New York with extensive operations throughout the world. Visit Pall at <http://www.pall.com/>.

CONTACTS:

Marcia Katz, Director of Public Relations
516.801.9128
Marcia_Katz@pall.com

Mike Mesawich, VP of Marketing
Pall Microelectronics
Ph: 516-801-9832
michael_mesawich@pall.com